Quantum Carrier Transport of Highly Disordered Electron System in Epitaxial Graphene on 6H-SiC with As-Grown Defects

Jaehyeong Jo¹, Eunseok Hyun¹, Jiwan Kim¹, Hyunjae Park¹, Junhyung Kim², Gahyun Choi³, So-Dam Sohn³, Jan Kunc⁴, Daejin Eom^{3*}, and Kibog Park^{1,5*}

¹Department of Physics, Ulsan National Institute of Science and Technology, Ulsan 44919, Republic of Korea ²Electronics and Telecommunications Research Institute, Daejeon 34129, Republic of Korea ³Korea Research Institute of Standards and Science, Daejeon 34113, Republic of Korea

⁴Institute of Physics, Charles University, Prague 2 CZ-121 16, Czech Republic

⁵Department of Electrical Engineering, Ulsan National Institute of Science and Technology, Ulsan 44919, Re-

public of Korea

*: d.eom@kriss.re.kr, kibogpark@unist.ac.kr

Ouantum-mechanical aspects of charge carrier transport in a highly disordered 2D electron system are nontrivial and fascinating in that they can be considered as a measure to estimate the degree of disorder in the system. Graphene is one of the most attractive 2D electron systems to investigate the quantum aspects of carrier transport because its magnetotransport characteristics of pristine high-quality crystalline phase are quite distinct from those of its disordered phase. To date, disordered graphene systems have mostly been prepared by well-defined artificial treatments to produce defects and decorate adatoms on high-quality single crystal. The defects in graphene, however, can also be created during the formation of graphene and their density can be modulated without additional post-treatments provided the graphene synthesis is elaborately controlled. Here, we report temperature-dependent magnetotransport characteristics of disordered epitaxial graphene (EG) films with as-grown defects on 6H-SiC (0001) substrates. The EG films are grown by metal-plate capping method [1], which is a kind of confinementcontrolled growth, and the growth parameters are finely adjusted to produce defects with varying densities. The defectiveness and inhomogeneity of grown film are characterized by analyzing D peak ($I_D/I_G = \sim 0.4$) in Raman spectrum. Atomic force microscopy (AFM) and scanning tunneling microscopy (STM) images on the EG films present irregular film morphology containing uneven step structures, pits on terraces, and point defects accompanied with relatively small sizes of grains. In magnetoresistance (MR) measurements at temperatures below 250 K, the monotonic negative MRs are observed for a wide range of out-of-plane magnetic field up to 9 T. Remarkably, the analytic fitting of weak localization (WL) correction [2] to the MR data indicates that WL is not completely suppressed even at 3 T below ~120 K despite a quite large carrier density $n > ~10^{13}$ cm⁻². In temperature-dependent resistivity measurements, the logarithmic increase after passing the minimum resistivity is observed as temperature goes down from room temperature. The temperature of minimum resistivity is $T_{min} \sim 116$ K when NO magnetic field is applied. Although the WL correction is considered, the logarithmic behavior still remains with the lowered T_{min} and it is attributed to electron-electron interaction (EEI) or Kondo effect [3]. In the broad temperature range from T_{min} to room temperature, on the other hand, the resistivity is T-linear [4], likely to indicate the dominancy of acoustic phonon scattering. Additionally, we will discuss about how more complex structural irregularity of monoand bi-layer regions coexisting in an EG film can be manifested in electrical properties of film by proposing an appropriate way for analyzing measured data.

References

[1] H. B. Jin et al., Sci. Rep. 5, 9615 (2015).

[2] E. McCann et. al., Phys. Rev. Lett. 97, 146805 (2006).

[3] J. Jobst et. al., Phys. Rev. B 88, 155412 (2013).

[4] E. H. Hwang et. al., Phys. Rev. B 77, 115449 (2008).

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